

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method for examination of nonuniformity defects of ~~patterns in a photomask pattern for manufacturing an image device, the photomask pattern including a repetitive pattern having a plurality of unit patterns arranged according to a regularity, the method comprising:~~

~~comprises—~~emitting light to the plurality of unit patterns to generate diffraction light at an edge portion of the repetitive pattern; ~~an examination object whose surface is provided with a repeating pattern in which unit patterns are arrayed in a regular fashion, photodetecting transmitted light or reflected light from the examination object, and observing the detected photodetection data to detect nonuniformity defects that have occurred in said repeating pattern, wherein~~

photodetecting the diffraction light to produce a photodetection data; and

observing the photodetection data to determine nonuniformity defects, the nonuniformity defects occurring in the plurality of unit patterns according to another regularity,

wherein the light comprises a monochromatic laser light having a wavelength of 500 to 570 nm, and

the nonuniformity defects are determined by identifying a disarrangement in the regularity of the photodetection data.

~~the method for examination of nonuniformity defects of patterns further comprises selecting and extracting light of one or a plurality of desired wavelength bands from light of a plurality of wavelength bands, and detecting nonuniformity defects of said repeating pattern by using the light of the selected and extracted wavelength bands.~~

2.-3. (Canceled)

4. (Currently Amended) A device for examination of nonuniformity defects in a photomask pattern of patterns for manufacturing an image device, the photomask pattern including a repetitive pattern having a plurality of unit patterns arranged according to a regularity, the device comprising:  
~~having~~ \_\_\_\_\_ a light source for emitting monochromatic laser light having a wavelength of 500 to 570 nm to the plurality of unit patterns to generate diffraction light at an edge portion of the repetitive pattern;~~to an examination object whose surface is provided with a repeating pattern in which unit patterns are arrayed in a regular fashion, and~~  
 \_\_\_\_\_ a photodetector for photodetecting the diffraction light to produce a photodetection data ~~transmitted light or reflected light from said examination object and converting the light into photodetection data, so that~~ that the nonuniformity defects, which occur in the plurality of unit patterns according to another regularity, are determined by identifying a disarrangement in the regularity of the photodetection data is observed to detect nonuniformity defects that have occurred in said repeating pattern, wherein  
 \_\_\_\_\_ ~~the device for examination of nonuniformity defects of patterns further has selection and extraction means for selecting and extracting light of one or a plurality of desired wavelength bands from the light of a plurality of wavelength bands, so that nonuniformity defects of said repeating pattern are detected using the light of the selected and extracted wavelength bands.~~

5.-8. (Canceled)

9. (Currently Amended) ~~The device for examination of nonuniformity defects of patterns according to claim 4, wherein said selection and extraction means is provided with~~ light source comprises a plurality of monochromatic light sources for individually emitting light of a desired wavelength band selected from the light of a plurality of wavelength bands,

~~and is configured to allow the light emission operation of the monochromatic light sources to be switched.~~

10.-20. (Canceled)